

Materials List for

Active Probe Atomic Force Microscopy with Quattro-Parallel Cantilever Arrays for High-Throughput Large-Scale Sample Inspection

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Materials

| Name | Company | Catalog Number | Comments |
|---|-------------------------|----------------|----------------------------|
| Active-Cantilever | nano analytik GmbH | AC-10-2012 | AFM Probe |
| E-Beam | EBX-30, INC | 012323-15 | Mask patterning instrument |
| Highly Oriented Pyrolytic Graphite – HOPG | TED PELLA, INC | 626-10 | AFM calibration sample |
| Mask Sample | Nanda Technologies GmbH | Test substrate | EUV Mask Sample substrate |
| NANO-COMPAS-PRO | nano analytik GmbH | 23-2016 | AFM Software |
| nanoMetronom 20 | nano analytik GmbH | 1-343-2020 | AFM Instrument |